

TOUCHSCREEN SERIES C FOR 8" WAFERS

AUTOMEGASAMDRI®-938

RECIPE CAPABLE WITH PROCESS DATA REVIEW

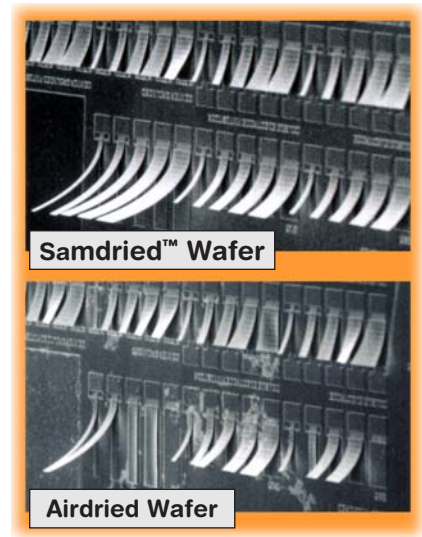
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• The New Supercritical Automegasamdri®-938 System was developed by our in-house design team whose goal was to listen to and incorporate your needs into our next generation.

• The classic features you have come to expect for decades that enable smooth operation, precise control and reproducibility are again evident in our most current design!

- **Process up to Five 8" Wafers per Process Run**
- **Touchscreen Programmable Interface**
- **First Time Ever...Previous Run Data Review**
- **Integrated Chiller Loop Decreases LCO₂ Consumption**
- **Easy Facilitation with Small Foot Print Design**

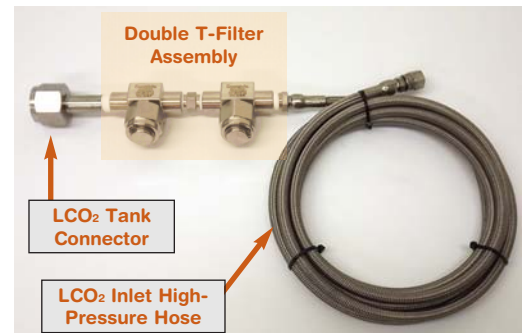


FEATURES

- A dedicated initial Slow Fill into the process chamber allows ideal fluid dynamics preserving the most sensitive micro devices.
- Maintenance made easy via accessible components including the external Post-Purge-Filter assembly.
- Patent Pending "Vortex Swirl": Non-mechanical stirring chamber allowing for fluid dynamic exchange without the need for particle generating friction causing devices.*
- Extremely Efficient integrated Closed Cooling Loop dropping chamber temperature quickly for shorter process run times.*
- The internal SOTER(tm) condenser* quietly captures and separates CO₂ exhaust and waste alcohols.
- Our original Chamber Inserts enable chamber I.D. variance of chamber I.D. maximizing efficiency in LCO₂ consumption, process time, and providing multiple size wafer process capability!
- Process chamber LCO₂ filtration down to 0.08µm with 99.999%+ particle retention.
- Processes up to five 8" wafers each run. Included are the following HF Compatible Wafer Holders: 8", 6", 4", 3", 2" and 10mm Die Holders.
- Chamber Illumination via viewing window facilitates chamber status visualization.*
- Automatic process with factory default recipe or the ability to customize your own!*
- All internal surfaces are inert to CO₂ and ultrapure alcohols.
- Repeatable operating parameters insuring "reproducibility" of results.
- Safety operation features integrated into both temperature and pressure automatic regulation.
- All electronic components meet CE, UL and/or U.S. Military Specifications.
- Clean room static-free compatible design.

SPECIFICATIONS

- Cabinet: 19.8" (50.3cm) Width x 31.7" (80.6cm) Depth x 44.5" (113.0cm) Height
- System Set-Up Area Footprint: 27" (68.6cm) Width x 38" (96.5cm) Depth
- Chamber size: 8.50" I.D. x 1.25" Depth / Chamber volume: 1162 ml
- 120V or 220V / 50-60Hz
- LCO₂ flow is precisely controlled through Micro Metering Valves with Vernier handles for adjustment ease.*



Standard Accessories

STANDARD ACCESSORIES

- High Pressure LCO₂ flexi-SS316 Braided line for safe operation and easy installation 10ft/3m length included with system. (Other lengths available upon request up to 100 ft /30m)
- Double T-Filter Assembly (#8785) pre-installed onto the chamber LCO₂ supply high-pressure hose.
- Static free exhaust tubing included for all exhaust ports.
- Spare chamber O-rings (3), chamber lamps (2), and slo-blow fuses (2x3A and 2x8A).
- Chamber Inserts included: 8" to 6" / 6" to 4" / 4" to 3" / 3" to 2" / 2" to 1.25" ! Allows for multiple wafer size drying.
- HF compatible wafer holders included: 8", 6", 4", 3", 2" and 10mm square die. Each holder can load up to five substrates each.
- 2 year warranty on all parts and labor.
- Free lifetime technical support.